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Education

8/2014 – present	Ph.D., Electrical Engineering Advisor: Prof. Mark J. Kushner	University of Michigan, Ann Arbor
9/2011 – 3/2014	M.E., Electronics Science & Technology Advisor: Prof. Jon Tomas Gudmundsson	Shanghai Jiao Tong University, China
8/2007 – 6/2011	B.E., Electrical Engineering & Its Automation	Southeast University, China

Refereed Journal Publications

1. S. Huang and J. T. Gudmundsson, Dual frequency capacitively coupled chlorine discharge, Plasma Sources Sci. Technol. **24**, 015003 (2015).
2. S. Huang and J. T. Gudmundsson, Ion energy and angular distributions in a dual-frequency capacitively coupled chlorine discharge, IEEE Trans. Plasma Sci. **42**, 2854 (2014).
3. S. Huang and J. T. Gudmundsson, A current driven capacitively coupled chlorine discharge, Plasma Sources Sci. Technol. **23**, 025015 (2014).
4. S. Huang and J. T. Gudmundsson, A particle-in-cell/Monte Carlo simulation of a capacitively coupled chlorine discharge, Plasma Sources Sci. Technol. **22**, 055020 (2013).

Contributed Conference Presentations

1. S. Huang, V. Volynets, S. Lee, I.-C. Song, S. Lu, J. R. Hamilton, J. Tennyson and M. J. Kushner, Insights to scaling remote plasma sources sustained in NF_3 mixtures, 62nd International Symposium of the American Vacuum Society, San Jose, California, October 2015.
2. S. Huang, V. Volynets, S. Lee, I.-C. Song, S. Lu, J. R. Hamilton, J. Tennyson and M. J. Kushner, Dry etching of Si_3N_4 using remote plasma sources sustained in NF_3 mixtures, 68th Gaseous Electronics Conference, Honolulu, Hawaii, October 2015.
3. S. Huang, J. R. Hamilton, J. Tennyson and M. J. Kushner, Remote plasma sources sustained in NF_3 mixtures, 22nd International Symposium on Plasma Chemistry, Antwerp, Belgium, July 2015.
4. J. T. Gudmundsson and S. Huang, A particle-in-cell/Monte Carlo simulation of a capacitively coupled chlorine discharge, 14th International Conference on Plasma Surface Engineering, Garmisch-Partenkirchen, Germany, September 2014.
5. S. Huang and J. T. Gudmundsson, Dual frequency capacitively coupled chlorine discharge, Gordon Research Seminar on Plasma Processing Science, Smithfield, Rhode Island, July 2014.
6. S. Huang and J. T. Gudmundsson, A particle-in-cell/Monte Carlo simulation of a capacitively coupled chlorine discharge, 41st IEEE International Conference on Plasma Science, Washington DC, May 2014.
7. J. T. Gudmundsson and S. Huang, A particle-in-cell/Monte Carlo simulation of a capacitively coupled chlorine discharge, 66th Gaseous Electronics Conference, Princeton, New Jersey, October 2013.